JUN 1 5 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: MEARS

Serial No. NOT YET ASSIGNED

Filing Date: HEREWITH

For: METHOD FOR MAKING

SEMICONDUCTOR DEVICE

INCLUDING BAND-ENGINEERED

SUPERLATTICE

I HEREBY CERTIFY THIS PAPER OR FEE IS BEING DEPOSITED WITH THE U.S. POSTAL SERVICE "EXPRESS MAIL POST OFFICE TO ADDRESSEE" SERVICE UNDER 37 CFR 1.10 ON THE DATE INDICATED BELOW AND IS ADDRESSED TO: MAIL STOP PATENT APPLICATIONS, P.O. BOX 1450, ALEXANDRIA, VA 22313-1450.

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DATE OF DEPOSIT: November 19, 2003

NAME: Justin Goree

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## CITATION UNDER 37 CFR §1.97

Mail Stop Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Attached is a form PTO-1449 listing several references for consideration in the examination of the above-identified application. A copy of each reference may be found in parent application, Serial No. 10/647,061 filed August 22, 2003. It is requested that these references be considered by the Examiner and officially made of record in accordance with the provisions of 37 CFR §1.97 and Section 609 of the MPEP.

Respectfully submitted,

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Atty Docket: Serial No.: Applicant: Filing Date: Group:

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			U.S. PA	TENT DOCUMENTS			
Examiner Initials		Document Number	Date	Name	Class	Sub Class	Filing Date
	AA	4,594,603	06/10/86	Holonyak, Jr.	357	16	01/24/85
	АВ	4,937,204	06/26/90	Ishibashi et al.	437	110	01/4/89
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		Document Number	Date	Country	Class	Sub Class	Translation
	AS	02/103767	12/27/02	wo	H01L	21/20	
	AT	2,347,520	09/06/00	GB	G02B	5/18	
	AU						

EXAMINER:	DATE CONSIDERED:

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 2 of 2

INFORMATION DISCLOSURE STATEMENT	Atty Docket: Serial No.: Applicant: Filing Date: Group:	62603_CON2 NOT YET ASSIGNED MEARS HEREWITH

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)			
Ť	AV	Xuan Luo et al.; "Chemical Design of Direct-Gap Light-Emitting Silicon", published July 25, 2002 by The American Physical Society; Vol. 89, Number 7	
	AW	R. Tsu; University of North Carolina at Charlotte, "Phenomena in Silicon Nanostructure Devices"; published 09/06/2000 © Springer-Verlag 2000	
	AX	P.D. Ye et al., "GaAs MOSFET with Oxide Gate Dielectric Grown by Atomic Layer Deposition"; © 2003 Agere Systems, March 2003	
	AY	Novikov et al.; "Silicon-based Optoelectronics" © 1999-2003 by John Wiley & Sons, Inc.; pp/ 1-6	
	AZ		
	ВА		

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